

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	968	134/902.ccls. and nozzle	US-PGPUB; USPAT	OR	ON	2005/09/16 13:08
L5	1147	134/902.ccls. and (nozzle or spray or jet)	US-PGPUB; USPAT	OR	ON	2005/09/16 13:08
L6	576	5 and valve	US-PGPUB; USPAT	OR	ON	2005/09/16 13:08
L7	222	6 and (plurality or multiple or several or few) near3 (nozzle or spray or jet)	US-PGPUB; USPAT	OR	ON	2005/09/16 13:08
L8	219	134/902.ccls. and rotat\$3 and nozzle near3 (multiple or array or plurality)	US-PGPUB; USPAT	OR	ON	2005/09/16 13:09
L9	98	7 not L8	US-PGPUB; USPAT	OR	ON	2005/09/16 14:02
L12	1813	Okuda.in.	US-PGPUB; USPAT	OR	ON	2005/09/16 14:02
L13	122	12 and wafer	US-PGPUB; USPAT	OR	ON	2005/09/16 14:45
L14	6	"6267516"	US-PGPUB; USPAT	OR	ON	2005/09/16 15:29
L15	1114	134/172,178,198.ccls.	US-PGPUB; USPAT	OR	ON	2005/09/16 15:30
L16	635	15 and nozzle	US-PGPUB; USPAT	OR	ON	2005/09/16 15:30
L17	163	16 and (wafer or substrate or semiconductor or workpiece)	US-PGPUB; USPAT	OR	ON	2005/09/16 15:30
S1	205	134/902.ccls. and (substrate or wafer or semiconductor or workpiece) and rotat\$3 and nozzle near3 (multiple or array or plurality)	US-PGPUB; USPAT	OR	ON	2005/09/16 07:54
S2	219	134/902.ccls. and rotat\$3 and nozzle near3 (multiple or array or plurality)	US-PGPUB; USPAT	OR	ON	2005/09/16 09:53
S3	28	134/902,94.1,98.1.ccls. and rotat\$3 near3 (substrate or wafer or semiconductor or workpiece) and nozzle near3 (multiple or array or plurality) and deionized near2 water and valve	US-PGPUB; USPAT	OR	ON	2005/09/16 10:07
S4	68	"134"/\$.ccls. and rotat\$3 near3 (substrate or wafer or semiconductor or workpiece) and nozzle near3 (multiple or plurality or several or array) and filter and valve and (radial or center)	US-PGPUB; USPAT	OR	ON	2005/09/16 10:40

S5	0	"134"/\$.ccls. and rotat\$3 near3 (substrate or wafer or semiconductor or workpiece) and nozzle near3 (multiple or plurality or several or array) and filter and valve	EPO; JPO; DERWENT	OR	ON	2005/09/16 10:40
S6	0	rotat\$3 near3 (substrate or wafer or semiconductor or workpiece) and nozzle near3 (multiple or plurality or several or array) and filter and valve	EPO; JPO; DERWENT	OR	ON	2005/09/16 10:41
S7	0	rotat\$3 and (substrate or wafer or semiconductor or workpiece) and nozzle near3 (multiple or plurality or several or array) and filter and valve	EPO; JPO; DERWENT	OR	ON	2005/09/16 10:41
S8	3	(substrate or wafer or semiconductor or workpiece) and nozzle near3 (multiple or plurality or several or array) and filter and valve	EPO; JPO; DERWENT	OR	ON	2005/09/16 10:41
S9	2036	(substrate or wafer or semiconductor or workpiece) and nozzle near3 (multiple or plurality or several or array)	EPO; JPO; DERWENT	OR	ON	2005/09/16 10:41
S10	16836	(substrate or wafer or semiconductor or workpiece) near3 rotat\$4and nozzle near3 (multiple or plurality or several or array)	EPO; JPO; DERWENT	OR	ON	2005/09/16 10:42
S11	114	(substrate or wafer or semiconductor or workpiece) near3 rotat\$4 and nozzle near3 (multiple or plurality or several or array)	EPO; JPO; DERWENT	OR	ON	2005/09/16 11:06
S12	2026	(substrate or wafer or semiconductor or workpiece) near3 rotat\$4 and nozzle near3 (multiple or plurality or several or array)	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/16 11:07
S13	330	S12 not S2 and valve and filter	US-PGPUB; USPAT; USOCR	OR	ON	2005/09/16 11:07